

Amendments to the Claims

1. (CURRENTLY AMENDED) A thin film patterning arrangement-(6), comprising a substrate (1) and barriers (3)-arranged to partition a surface of the substrate (1) into sub-areas (5), characterised in that at least said surface is of polymeric material, and said surface is at least partly coated with at least partly inorganic coating (2).

2. (CURRENTLY AMENDED) An arrangement (6)-according to claim 1, wherein said at least partly inorganic coating (2)-comprises 100 % inorganic material.

3. (CURRENTLY AMENDED) An arrangement (6)-according to claim 1, wherein said at least partly inorganic coating (2)-comprises at least 5 % inorganic material.

4. (CURRENTLY AMENDED) An arrangement (6)-according to ~~any of the preceding claims, claim 1,~~ wherein said at least partly inorganic coating (2)-comprises at least two separate coating materials.

5. (CURRENTLY AMENDED) An arrangement (6)-according to ~~any of the preceding claims, claim 1,~~ wherein after a surface treatment, a difference in advancing contact angle of at least 10 degrees between the surface of said at least partly inorganic coating (2) and the surfaces of said barriers (3)-is established.

6. (CURRENTLY AMENDED) An arrangement (6)-according to ~~any of the preceding claims, claim 1,~~ wherein said at least partly inorganic coating (2)-is more than 70% transparent.

7. (CURRENTLY AMENDED) A method for producing a thin film patterning arrangement-(6), comprising:

- supplying a substrate (1)-with at least a surface of polymeric material,
- coating at least a part of said surface of said substrate (1)-with an at

least partly inorganic coating (2), and

- depositing barriers (3) on said at least one coated surface.

8. (CURRENTLY AMENDED) A method according to claim 7, further comprising:

- subjecting said at least partly inorganic coating (2) and said barriers (3) to a surface treatment.

9. (ORIGINAL) A method according to claim 8, wherein said surface treatment comprises plasma treatment.

10. (CURRENTLY AMENDED) A thin film device comprising a thin film patterning arrangement (6) according to ~~any of the claims 1-6~~claim 1, or a thin film patterning arrangement obtainable by the method according to ~~any of the claims 7 to 9~~claim 7, further comprising thin film material (4) deposited on at least part of said sub-areas (5).

11. (CURRENTLY AMENDED) A thin film device according to claim 10, wherein said thin film material (4) forms at least one thin film pattern selected from the group comprising optical patterns, conductor patterns, insulator patterns, semiconductor patterns and combinations thereof.

12. (ORIGINAL) A thin film device according to claim 11, wherein said thin film pattern is an optical pattern and said device is a colour filter.

13. (CURRENTLY AMENDED) A method for manufacture of a thin film device, comprising:

- providing a thin film patterning arrangement (6) according to ~~any of the claims 1 to 6~~claim 1, or a thin film patterning arrangement (6) obtainable by a method according to ~~any of the claims 7 to 9~~claim 7, and
- depositing at least one thin film material (4) on at least part of said sub-areas (5).

14. (CURRENTLY AMENDED) A method according to claim 12 wherein said depositing of thin film material (4) comprises:

- ink jet printing of a liquid comprising said thin film material (4).

15. (CURRENTLY AMENDED) A display device comprising a thin film patterning arrangement (6) according to ~~any of the claims 1 to 6, claim 1~~ a thin film patterning arrangement (6)-obtainable by a method according to ~~any of the claims 7 to 9, claim 7~~, a thin film device according to ~~any of the claims 10 to 12, claim 10~~, or a thin film device obtainable by a method according to ~~any of the claims 13 to 14, claim 13~~.